EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	"7166336".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/17 14:24
L2	19	("20020055012" "20030124229" "20030207115" "20050003124" "20050019577" "20050155553" "20050266191" "20060051539" "4809876" "5798139" "4809876" "5798139" "6844225" "6294226" "6589619" "6805931" "6827972" "6854309" "6919114" "6924001" "7029752").PN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/12/17 14:24
L3	4832	DLC and electrode	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/12/17 14:27
L4	14044	housing same ((plural \$3 or multi\$3 or two or three or four) near container or bottle)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/12/17 14:27
L5	7	3 and 4	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/12/17 14:27
L6	2	"6294226".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/17 15:04
S1	0	rotary and cvd and cahmber and (plastic) and house\$3 and source gas and electrode and insulate \$3 and frequency	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 11:59
S2	25	rotary and cvd and chamber and (plastic) and house\$3 and source gas and electrode and insulate \$3 and frequency	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 12:00

S3	9516	(cvd or chemical vapor deposition) and chamber and housing	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 12:03
S 4	73	S3 and plastic container	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 12:03
S 5	336	\$3 and (housing near (plural\$3 or multiple \$3))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 12:04
S 6	217	S5 and insulat\$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 12:04
S 7	91	S6 and (plastic)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 12:05
S 8	13	S5 and (housing near (two or three or four))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 12:07
S9	2	"6924001".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 13:25
S10	693	column near electrode and (cvd or dlc)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 14:44
S11	798	(column\$2 or column \$shaped or columnar body) near electrode and (cvd or dlc)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 14:45
S12	0	S11 and aparatus	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 14:45

S13	304	S11 and apparatus	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 14:45
S14	53	S13 and (housing or house\$3) and (plastic)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 14:46
S15	2	"5522935".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 14:49
S16	0	10-258825 A	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 14:53
S17	36676	plastic and housing and electrode	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:10
S18	21545	S17 and apparatus	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:10
S19	573	S18 and (housing near (plural\$3 or multiple \$3))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:11
S20	234	S19 and insulating	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:11
S21	357	S19 and insulat\$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:11
S22	163	S21 and frequency	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:11

S 23	8	S22 and source gas	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:12
S24	18	S19 and (electrode near (interal or external))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:13
S25	98	plastic near (plural\$3 near housing)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:14
S26	17	S25 and electrode	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:15
S27	107	plastic container near housing	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:15
S28	121	(plural\$3 or multiple) near (housing or enclosure) near electrode	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/12 15:16
S29	7769	external electrode and internal electrode	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/16 11:23
S30	251	S29 and ((DLC or diamond like carbon) or (CVD or chemical vapor deposition))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/16 11:24
S31	142	S30 and apparatus	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/16 11:24
S32	27	S31 and housing	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/16 11:24

S33	88	S31 and (plurality or multiple)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/16 11:25
S34	637	(plural\$3 or multiple) near housing same electrode	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/16 11:51
S35	3	(plural\$3 or multiple) near (housing or enclosure) same internal electrode	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/16 11:51
S39	97076	(CVD or chemical vapor deposition) and apparatus	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:48
S40	4650451	rotary or rotat\$6	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:49
S41	31331	S39 and S40	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:49
S42	313456	chamber and film	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:49
S43	14982	S41 and S42	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:49
S44	1915983	electrode	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:49
S45	45698	S44 near (external or internal)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:49

S47	224	S43 and S45	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:50
S48	88192	plural\$4 near (chamber or hous\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:50
S49	5	S47 and S48	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:50
S50	2	"6294226".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:51
S51	28	S39 and S42 and S45 and S48	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:53
S52	511542	((CVD or chemical vapor deposition) or (DLC or diamond\$like \$carbon) or deposit\$4) and apparatus	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:54
S53	22	S52 and S40 and S42 and S45 and S48	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/11 16:55

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